



## Legionella Growth Supplement (BCYE)

FD142

A chemical enrichment supplement recommended for enhancing growth of *Legionella* species.

### Composition

Per vial sufficient for 440 ml medium

Ingredients	Concentration
ACES buffer/ Potassium hydroxide	5g
Ferric pyrophosphate, soluble	0.125g
L-cysteine hydrochloride	0.20g
alpha-Ketoglutarate	0.50g
Distilled water	50 ml

### Directions:

Warm up the refrigerated supplement to 45-50°C, shake well to form uniform suspension. Avoid frothing. Aseptically add to 440 ml sterile, molten, cooled (45-50°C) Legionella Agar Base [M809A](#) . If desired aseptically add rehydrated contents of 1 vial of Legionella (GVPC) Selective Supplement [FD143](#) . Mix well and pour into sterile petri plates. The final pH of the medium will be  $6.9 \pm 0.2$ . In case of non incorporation of Legionella (GVPC) Selective Supplement [FD143](#) , add aseptically 10 ml sterile distilled water to bring the total volume to 500 ml medium.

Note:

On storage at 2 to 8°C; due to combination of ingredients, slight fine precipitate may develop which may be evenly distributed before addition to medium.

### Storage and Shelf Life

Store at 2-8°C. Use before the expiry date on the label.

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### Disclaimer :

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